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(54) Title: CURABLE LIQUID RESIN COMPOSITION

(57) Abstract: The invention relates to a curable liquid resin composition comprising the following components (A), (B), and (C): 0.5-50 wt% of a urethane (meth)acrylate oligomer obtained from a polyol (a) having a branched structure comprising at least one branch point and at least three molecular chains extending from that branch point, said molecular chains having a molecular weight of 200 g/mol or more, including a hydroxyl group at the terminal of at least two molecular chains extending from the branch point, a polyisocyanate (b), and a hydroxyl group-containing (meth)acrylate (c); (B) 5-90 wt% of a polymerizable organic compound; and (C) 0.1-10 wt% of a polymerization initiator, wherein the cured product has a Young's modulus of 350 MPa or more at 23°C.

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